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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/768,747	01/23/2004	Martin Peckerar	83,028	7954	
75	90 06/06/2006		EXAMINER		
Naval Research Laboratory			GUERRERO, MARIA F		
4555 Overlook Code 1008.2	Overlook Ave., S.W. ART UNIT PAP		PAPER NUMBER		
	C 20375-5320		2822		

DATE MAILED: 06/06/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

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* .		Applicati n N .	Applicant(s)	
		10/768,747	PECKERAR ET AL.	
Offic Ac	tion Summary	Examin r	Art Unit	
		Maria Guerrero	2822	
The MAILING I	DATE of this communication app	pears n the cover sheet with the c	rrespondence address	ŧ,
WHICHEVER IS LON  - Extensions of time may be a after SIX (6) MONTHS from  - If NO period for reply is spe  - Failure to reply within the se Any reply received by the O	NGER, FROM THE MAILING DA available under the provisions of 37 CFR 1.13 in the mailing date of this communication. scified above, the maximum statutory period we et or extended period for reply will, by statute,	Y IS SET TO EXPIRE 3 MONTH( ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be time will apply and will expire SIX (6) MONTHS from the cause the application to become ABANDONE to date of this communication, even if timely filed	N. nely filed the mailing date of this communicatio D (35 U.S.C. § 133).	
Status				
1) Responsive to	communication(s) filed on 24 M	arch 2006.		
2a)⊠ This action is <b>F</b>		action is non-final.		
3) Since this appli	cation is in condition for allowar	nce except for formal matters, pro	secution as to the merits is	5
closed in accor-	dance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	53 O.G. 213.	
Disposition of Claims				
4)⊠ Claim(s) <i>1-20</i> is	s/are pending in the application.			
	e claim(s) <u>15-20</u> is/are withdraw			
5) Claim(s)	is/are allowed.			
6)⊠ Claim(s) <u>1-14</u> is	s/are rejected.			
7) Claim(s)	is/are objected to.			
8) Claim(s)	are subject to restriction and/or	r election requirement.		
Application Papers				
9) The specification	n is objected to by the Examine	r.		
·	•	epted or b) objected to by the E	Examiner.	
Applicant may no	ot request that any objection to the	drawing(s) be held in abeyance. See	37 CFR 1.85(a).	
Replacement dra	wing sheet(s) including the correcti	ion is required if the drawing(s) is obj	ected to. See 37 CFR 1.121(	d).
11) The oath or dec	laration is objected to by the Ex	aminer. Note the attached Office	Action or form PTO-152.	
Priority under 35 U.S.C.	§ 119			
	nt is made of a claim for foreign me * c)∐ None of:	priority under 35 U.S.C. § 119(a)	-(d) or (f).	
	copies of the priority documents			
		s have been received in Application		
		ity documents have been receive	ed in this National Stage	
• •	on from the International Bureau	• • • • • • • • • • • • • • • • • • • •		
* See the attached	detailed Office action for a list of	of the certified copies not receive	d.	
Attachment(s)				
1) Notice of References Cite		4) Interview Summary		
	Patent Drawing Review (PTO-948) tatement(s) (PTO-1449 or PTO/SB/08)	Paper No(s)/Mail Da 5) Notice of Informal Pa	ate atent Application (PTO-152)	
Paper No(s)/Mail Date		6) Other:		

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#### **DETAILED ACTION**

1. This Office Action is in response to the Amendment filed December 20, 2005 and the Election filed March 24, 2006.

#### **Status of Claims**

2. Claims 1-20 are pending.

### Election/Restrictions

- 3. Applicant's election of Group I (claims 1-14) in the reply filed on March 24, 2006 is acknowledged. Because applicant did not distinctly and specifically point out the supposed errors in the restriction requirement, the election has been treated as an election without traverse (MPEP § 818.03(a)).
- 4. Claims 15-20 are withdrawn from further consideration pursuant to 37 CFR 1.142(b) as being drawn to a nonelected invention, there being no allowable generic or linking claim. Election was made without traverse in the reply filed on March 24, 2006.

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of

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the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

- 5. Claims 1-14 are rejected under 35 U.S.C. 103(a) as being unpatentable over Davis et al. (US 6,051,849) in view of Edmond et al. (US 5,093,576).
- 6. Davis et al. teaches a method of making a device comprising the steps of: (a) depositing a dielectric thin film mask material (silicon oxide) on a semiconductor substrate (sapphire, silicon carbide) surface; (b) patterning the mask material to form openings therein extending to the substrate surface; (c) growing active material (gallium nitride) in the openings by confined epitaxy; (d) removing the mask material to form the device with reduced extended defect density; and (e) depositing electrical contacts on the device (Abstract, Fig. 1-5, col. 2, lines 24-65, col. 3, lines 25-67, col. 4, lines 1-65, col. 6, lines 40-57).
- 7. Davis et al. discloses the steps of: cleaning the exposed substrate surface to make it ready for epitaxial deposition of the active material, doping the active material, depositing a resist material on the mask material, developing the resist material, and creating the openings. Davis et al. shows the substrate surface including a thin film of a starting material and the mask material having 1000 Angstroms (col. 3, lines 25-65, col. 4, lines 1-67).

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8. Davis et al. teaches forming a device having reduced extended defect density comprising a substrate (sapphire), forming a semiconductor active material (gallium nitride) deposited on said substrate and having atomically smooth surfaces, forming electrical contacts on said device and providing at least one electronic device in the grown active material (Abstract, Fig. 1-5, col. 2, lines 24-55, col. 3, lines 25-67, col. 4, lines 1-65, col. 6, lines 40-57).

Davis et al. does not specifically show the rate, bandgap, frequency, power and current as claimed. However, one of ordinary skill in the art would have found it prima facie obvious at the time of the invention to include these variables merely by following the teachings of the reference. In this regard, it is well settled that it is not inventive to determine (by mere routine experimentation) the optimum values of a result-effective variable. In re Peterson, 315 F.3d 1325, 1330, 65 USPQ2d 1379, 1382 (Fed. Cir, 2003)("The normal desire of scientist or artisans to determine where in a disclosed set of percentage ranges is the optimum combination of percentages."); In re Boesch, 617 F.2d 272, 276, 205 USPQ 215, 219 (CCPA 1980) ("Discovery of an optimum value of a result effective variable in a known process is ordinarily within the skill of the art."); In re Aller 220 F. 2d 454, 456, 105 USPQ 233, 235, (CCPA 1955)("Where the general conditions of a claim are discloses in the prior art, it is not inventive to discover the optimum or workable ranges by routine experimentation.")

In addition, Edmond et al. is cited as evidence to show that the device having reverse bias leakage current of less than 1x 10-9 amps is conventionally desired in the

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art (Abstract, Fig. 6, col. 2, lines 40-65, col. 4, lines 50-68, col. 5, lines 1-50, col. 12, lines 15-25, col. 14, lines 45-68).

Therefore, it would have been obvious to a person of ordinary skill in the art at the time of the invention to include the rate, thickness, bandgap, frequency, power and current in Davis et al. reference by routine experimentation because there is not evidence of unexpected results and to specify the device having the leakage current of less than 1x 10-9 amps as taught by Edmond et al. in order to provide a device having reasonably sensitivity (Edmond et al., col. 3, lines 25-40, col. 5, lines 1-8).

# Response to Arguments

9. Applicant's arguments with respect to claims 1-14 have been considered but are moot in view of the new ground(s) of rejection.

## Conclusion

- 10. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Davis et al. "Gallium Nitride Materials-Progress, Status, and Potential Roadblocks"; Zheleva et al. "Dislocation density reduction via lateral epitaxy in selectively grown GaN structures"; Goto et al. (US 5,741,360); Fuller (US 4,971,928); Nakamura et al. (US 5,543,629) and Nakamura et al. (US 5,847,418) show several embodiments related to applicant's disclosure.
- 11. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP

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§ 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

12. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Maria Guerrero whose telephone number is 571-272-1837.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Zandra Smith can be reached on 571-272-2429. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

May 30, 2006

MARIA F. GUERRERO PRIMARY EXAMINER